IN THE UNITED STATES PATENT AL

Attn: OIPE

Application of

Makoto KOBAYASHI et al.

Application No.:

09/830,434

Docket No.:

109352

Filed: April 26, 2001

For:

POLISHING PAD AND POLISHING METHOD FOR SEMICONDUCTOR WA

REQUEST FOR CORRECTION OF PALM RECORDS

Director of the U.S. Patent and Trademark Office Washington, D.C. 20231

Sir:

Attached is a photocopy of the original filing receipt on which errors have been corrected in red. These errors are being brought to the attention of the Patent and Trademark Office so that it may correct its records.

Respectfully submitted

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Date: November 20, 2001

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Applicant(s)

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Domestic Priority data as claimed by applicant

Assignment For Pulished Patent Application Shin-Etsu Handotai Co., Ltd., Tokyo, Japan

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Preliminary Class

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